Introduction to Lithography:
Fabrication of Team Spirit Silhouettes

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Photolithography (also termed "optical lithography" or "UV lithography") is a process used in microfabrication to selectively remove parts of a thin film or the bulk of a substrate. It uses light to transfer a geometric pattern from a photomask to a light-sensitive chemical "photoresist", or simply "resist," on the substrate.
SU-8 photoresist

SU-8 is a commonly used epoxy-based **negative** photoresist. The molecule is as below:

Upon **exposure to UV (365 nm) radiation**, a strong acid (HSbF₆) is generated which causes the epoxy resin **to form a ladder-like structure with a high cross-linking density** when heated above a critical temperature provided in a post-exposure bake.
Personal Protective Equipment (PPE): nitrile gloves and UV goggles.

Reference:
Title: *Introduction to photolithography: Preparation of microscale polymer silhouettes*
Author(s): Berkowski KL; Plunkett KN; Yu Q; et al.
Source: JOURNAL OF CHEMICAL EDUCATION Volume: 82 Issue: 9 Pages: 1365-1369
Published: SEP 2005.